

L Number	Hits	Search Text	DB	Time stamp
1	5191	(250/492.22,492.2,492.3).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:19
2	20407	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:20
3	511	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:49
4	425	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and control near1 signal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:22
5	425	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:22
6	35	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)) and ((storage or store or storing) near1 (control near signal)) and (shift near register\$4)) and ((plurality or multiple) near4 beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:27
8	2	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)) and ((storage or store or storing) near1 (control near signal))) and (shift near register\$4)) and ((plurality or multiple) near4 beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:24
7	10	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)) and ((storage or store or storing) near1 (control near signal))) and (shift near register\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:25
9	3	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (control near1 signal)) and ((storage or store or storing) near1 (control near signal))) and ((250/492.22,492.2,492.3).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:28
10	35	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:29
11	14	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))) and (deflect\$4 near2 control\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:31
12	1	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))) and (deflect\$4 near2 control\$4)) and ((250/492.22,492.2,492.3).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:32

13	6071	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:33
14	3551	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:34
15	973	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:34
16	345	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near signal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:40
18	2	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near signal)) and (control\$4 near signal near storage)) and (stor\$4 near5 deflect\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:36
17	3	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near signal)) and (control\$4 near signal near storage)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:40
19	703	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (control\$4 near signal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:40
20	5	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (control\$4 near signal)) and (control\$4 near signal near storage)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:41
21	17	Hashimoto near Shin-Ichi	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:41
22	6121	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:50
23	103	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:51
24	37	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal))) and (deflect\$5 near control\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:51

25	16	((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))) and (deflect\$5 near control\$4)) and (substrate or wafer or semiconductor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:52
26	10	((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))) and (deflect\$5 near control\$4)) and (substrate or wafer or semiconductor)) and (electrode or deflector)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:52

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1	5191	(250/492.22,492.2,492.3).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:19
2	20407	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:49
3	511	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near\$4 signal near\$4 stor\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:49
4	425	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near\$4 signal near\$4 stor\$4)) and control near\$4 signal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:22
5	425	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near\$4 signal near\$4 stor\$4)) and (control near\$4 signal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:22
6	35	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near\$4 signal near\$4 stor\$4)) and (control near\$4 signal)) and ((storage or store or storing) near\$4 (control near\$4 signal))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:27
8	2	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near\$4 signal near\$4 stor\$4)) and (control near\$4 signal)) and ((storage or store or storing) near\$4 (control near\$4 signal)) and (shift near\$4 register\$4)) and ((plurality or multiple) near\$4 beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:24
7	10	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near\$4 signal near\$4 stor\$4)) and (control near\$4 signal)) and ((storage or store or storing) near\$4 (control near\$4 signal)) and (shift near\$4 register\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:25
9	3	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near\$4 signal near\$4 stor\$4)) and (control near\$4 signal)) and ((storage or store or storing) near\$4 (control near\$4 signal)) and ((250/492.22,492.2,492.3).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:28
10	35	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:29
11	14	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))) and (deflect\$4 near\$2 control\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:31
12	1	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control adj signal adj (storage or stor\$3))) and (deflect\$4 near\$2 control\$4)) and ((250/492.22,492.2,492.3).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:32

13	6071	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:33
14	3551	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:34
15	973	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:34
16	345	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near signal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:40
18	2	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near signal)) and (control\$4 near signal near storage)) and (stor\$4 near5 deflect\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:36
17	3	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (deflect\$5 near2 control\$4)) and (control\$4 near signal)) and (control\$4 near signal near storage)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:40
19	703	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (control\$4 near signal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:40
20	5	((electron or charged-particle or (charged adj particle)) near (beam or expos\$4)) and deflector) and (wafer or substrate or sample)) and (control\$4 near signal)) and (control\$4 near signal near storage)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:41
21	17	Hashimoto near Shin-Ichi	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:41
22	6121	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:50
23	103	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:59
24	37	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal))) and (deflect\$5 near control\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:51

25	16	((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))) and (deflect\$5 near control\$4)) and (substrate or wafer or semiconductor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 14:52
26	10	((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))) and (deflect\$5 near control\$4)) and (substrate or wafer or semiconductor)) and (electrode or deflector)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:45
27	7	(((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near2 signal)) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))) and (deflect\$5 near control\$4)) and (substrate or wafer or semiconductor)) and (electrode or deflector)) and register	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:45
28	150	((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:50
29	46	(((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:57
30	18	(((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:51
31	13	((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:51
32	6	(((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and switch\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:53
34	1	(((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and switch\$4) and binary) and analog	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:52

33	3	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and switch\$4) and binary	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:52
35	5	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and (clock or timer or timing)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:01
36	2	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and (clock or timer or timing)) and (shift near register)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:57
37	1	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and (clock or timer or timing)) and (shift near register)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:55
38	1	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and (clock or timer or timing)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:58
39	3	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and (shift near register)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:56
40	1	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and (shift near register)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:56

41	1	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and ((plurality or multiple or two) near4 (beam or beamlet))) and expos\$4) and (wafer or substrate or sample or semiconductor)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:57
42	28	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:57
43	7	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)) and ((plurality or multiple or two) near4 (beam or beamlet)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:59
44	3	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (stor\$4 near4 deflect\$4 near4 (signal or output))) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)) and ((plurality or multiple or two) near4 (beam or beamlet))) and (shift near register)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:58
45	68	((250/492.22,492.2,492.3).CCLS.) and (shift near register)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:58
46	13	((250/492.22,492.2,492.3).CCLS.) and (shift near register)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 16:58
48	1	(((((250/492.22,492.2,492.3).CCLS.) and (shift near register)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)) and ((plurality or multiple or two) near4 (beam or beamlet))) and (stor\$4 near ((control or deflect\$4) near2 (output or signal)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:25
47	7	(((((250/492.22,492.2,492.3).CCLS.) and (shift near register)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)) and ((plurality or multiple or two) near4 (beam or beamlet)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:00
49	5	(((((250/492.22,492.2,492.3).CCLS.) and (shift near register)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)) and ((plurality or multiple or two) near4 (beam or beamlet))) and deflect\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:00
50	5	(((((250/492.22,492.2,492.3).CCLS.) and (shift near register)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)) and ((plurality or multiple or two) near4 (beam or beamlet))) and deflect\$4) and stor\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:00
51	5	(((((250/492.22,492.2,492.3).CCLS.) and (shift near register)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)) and ((plurality or multiple or two) near4 (beam or beamlet))) and deflect\$4) and stor\$4) and (clock or timer or timing)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:01

52	2	(((((250/492.22,492.2,492.3).CCLS.) and (shift near register)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)) and ((plurality or multiple or two) near4 (beam or beamlet))) and deflect\$4) and stor\$4) and (clock or timer or timing)) and (stor\$4 near5 deflect\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:02
53	3	(((((250/492.22,492.2,492.3).CCLS.) and (shift near register)) and (flipflop\$4 or (flip adj flop) or flip-flop\$4)) and ((plurality or multiple or two) near4 (beam or beamlet))) and deflect\$4) and stor\$4) and (clock or timer or timing)) and (stor\$4 near5 (signal or output))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:02
54	86	((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (stor\$4 near4 (deflect\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:26
55	42	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (stor\$4 near4 (deflect\$4))) and binary	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:26
56	34	(((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (stor\$4 near4 (deflect\$4))) and binary) and analog	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:26
58	1	((((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (stor\$4 near4 (deflect\$4))) and binary) and analog) and (identif\$4 with deflect\$4)) and ((diagnos\$4 or analyz\$4) with deflector)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:27
57	3	((((((((electron or charged-particle or (charged adj particle))near beam) and deflect\$4 and control\$4) and (control\$4 near4 signal near4 stor\$4)) and (stor\$4 near4 (deflect\$4))) and binary) and analog) and (identif\$4 with deflect\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/04 17:28